

Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. MI22-1913		SERIAL NO. 10/050,334	
<div style="border: 1px solid black; border-radius: 50%; padding: 10px; display: inline-block;"> <p style="margin: 0;">LIST OF ART CITED BY APPLICANT (Use separate sheets if necessary)</p> <p style="margin: 0; font-size: 0.8em;">JUL 11 2005</p> </div>				APPLICANT: Vishnu K. Agarwal et al.			
				FILING DATE January 15, 2002		GROUP 2813	
U.S. PATENT DOCUMENTS							
Examiner's Initials	Document Number	Date	Name	Class	Subclass	Filing Date if Appropriate	
TN	AA	6,359,295 B2	03/2002	Yang et al.			
	AB	6,403,156	06/2002	Jang			
	AC	6,596,602 B2	07/2003	Lizuka et al.			
	AD	6,627,462 B1	09/2003	Yang et al.			
	AE	6,664,186 B1	12/2003	Callegari et al.			
TN	AF	6,746,930	06/2004	Yang			
	AG						
TN TN	AH	2002/0142488	10/2002	Hong, Suk-Kyoung			
	AI	2002/0109198 A1	08/2002	Yang et al.			
FOREIGN PATENT DOCUMENTS							
	Document Number	Date	Country	Class	Subclass	Translation	
						Yes	No
TN TN	AJ	KR 2002046433	05/2003	Lee, J.W.			
	AK	EP 1 508 906 A2	02/2005	Lee et al.			
	AL						
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)							
TN	AM	Ritala et al.; <i>Perfectly Conformal TiN and Al2O3 Films Deposited by Atomic Layer Deposition</i> ; Chemical Vapor Deposition, v. 5, No. 1, 1999, pp. 7-9.					
	AN						
	AO						
EXAMINER <i>T. N. [Signature]</i>		DATE CONSIDERED <i>11/9/05</i>					
<p><small>*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.</small></p>							